

POLISHING APPARATUS AND PROGRAM

Abstract

A polishing apparatus comprises:

a generation unit configured to generate time-series data of a feature value up to a target time point by using data regarding a frictional force between a polishing member and a target substrate up to the target time point during polishing or a temperature measurement data of the polishing member or the target substrate; and

an prediction unit configured to input at least the time-series data of the feature value generated by the generation unit to a machine learning model trained with a training data set, and output an predicted value of a polishing amount or a residual film amount at the target time point during polishing of the target substrate.

Figure 5A